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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Tsunehiro NISHI et al.

Confirmation No.: 4806

Serial No.: 10/073,223

Examiner: Sin J. Lee

Filed: February 13, 2002

Group Art Unit: 1752

Title: POLYMER, RESIST COMPOSITION AND PATTERNING PROCESS

REPLY AFTER FINAL REJECTION

Mail Stop AF

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Final Office Action mailed April 12, 2004, kindly amend the above-identified application as follows.

Amendments and additions to the **Claims** are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 17 of this paper.